

NEGATIVE TYPE FLUORINE-CONTAINING RESIST COMPOSITION

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Abstract of JP2002090996

PROBLEM TO BE SOLVED: To provide a negative type resist composition excellent in transparency particularly to radiation and dry etching resistance as a chemical amplification type resist and giving a resist pattern excellent in sensitivity, resolution, flatness, heat resistance, etc.

SOLUTION: The negative type fluorine-containing resist composition contains a fluoropolymer (X) having a monomer unit containing an acidic hydroxyl group as a constitutional unit, an acid generating compound (Y) which generates an acid when irradiated with light, an aminoplast (Z) and an organic solvent (D).

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